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	Application No.	Applicant(s)	
N. C C. Allannakilika	10/017,396	ENDO, KAZUHIKO	
Notice of Allowability	Examiner	Art Unit	
	Yennhu B. Huynh	2813	
The MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIG	(OR REMAINS) CLOSED in this apport or other appropriate communication GHTS. This application is subject to	olication. If not includ will be mailed in due	ed course. THIS
1. This communication is responsive to 10/15/04.			
2.  The allowed claim(s) is/are <u>1-14,16 and 17</u> .			
3. $igotimes$ The drawings filed on <u>18 December 2004</u> are accepted by t	the Examiner.		
4. Acknowledgment is made of a claim for foreign priority una   All   b)  Some*   c)  None   None	been received.  been received in Application No cuments have been received in this communication to file a reply ENT of this application.  tted. Note the attached EXAMINER' as reason(s) why the oath or declarate to be submitted. on's Patent Drawing Review (PTO- Amendment / Comment or in the Comment or in the Comment of the drawing he header according to 37 CFR 1.121(content).	complying with the recomplying that action of the recomplying in the front (not the recomplying in the front (not the recomplying in the submitted.)	quirements
Attachment(s)  1. ☐ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/06 Paper No./Mail Date 12/18/01  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	5.  Notice of Informal P 6.  Interview Summary Paper No./Mail Dat 8), 7.  Examiner's Amendr 8.  Examiner's Stateme 9.  Other CARL WHITEH	(PTO-413), te nent/Comment ent of Reasons for Allo EAD, JR.	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) **TECHNOLOGY CENTER 2800** 

Application/Control Number: 10/017,396

Art Unit: 2813

### **DETAILED ACTION**

This Office Action is in response to the Amendment filed on 10/15/04.

Claims 15, 18 & 19 are cancelled by the Amendment filed on 10/15/04.

## **Priority**

Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

#### Oath/Declaration

Oath/Declaration filed on 12/18/01 is accepted.

### Information Disclosure Statement

The information disclosure statement filed on 12/18/01 is being considered by the examiner.

### **EXAMINER'S AMENDMENT**

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Thomas Perkins on 12/18/04.

The application has been amended as followed: Cancel claim numbers 20-38.

The title of the invention is not descriptive. A new title is required that is clearly indicative of the invention to which the claims are directed.

Art Unit: 2813

The title is as followed: Method of Forming A Silica Insulation Film With A Reduced Dielectric Constant.

## Claim Rejections - 35 USC § 102

Claims amended overcome rejections. Rejections withdrawn.

# Claim Rejections - 35 USC § 103

Claims amended overcome rejections. Rejections withdrawn.

### Allowable Subject Matter

Claims 1-14, 16 & 17 are allowable over prior art of record.

The following is an examiner's statement of reasons for allowance: Prior art do not disclose a silica insulation film with reduced dielectric constant, which includes the steps of carrying out a chemical vapor deposition at not less than 500 C degrees to cause elimination reaction of the benzene nucleuses at the same time of deposition of the insulator, thereby to form the insulator including pores, in combination with other limitations (cl.1 ); wherein a main component of silicon dioxide, formed by a CVD, having at least one kind of organic substance including benzene nucleuses is used as a benzene nucleus source so that the insulator includes the benzene nucleuses, and wherein the benzene nucleuses are removed by causing a combustion reaction in an oxygen atmosphere, in combination with other limitations (cl.13); and wherein the insulator has been formed by the CVD, then the benzene nucleuses are removed from the insulator thereby to form pore in the insulator, and wherein the elimination reaction

is caused by exposed to oxygen radicals generated in a plasma, in combination with other limitations (cl.14).

The above limitations for claims 1, 13 & 14 are neither anticipated nor rendered obvious over the prior art of record.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on statement of Reasons for Allowance.

#### Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Yennhu B Huynh whose telephone number is 571-272-1692. The examiner can normally be reached on 8.30AM-7.00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead, Jr., can be reached on 571-272-1702. The fax phone numbers for the organization where this application or proceeding is assigned are 703-308-7722 for regular communications and 703-308-7722 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-7724.

YNBH,

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